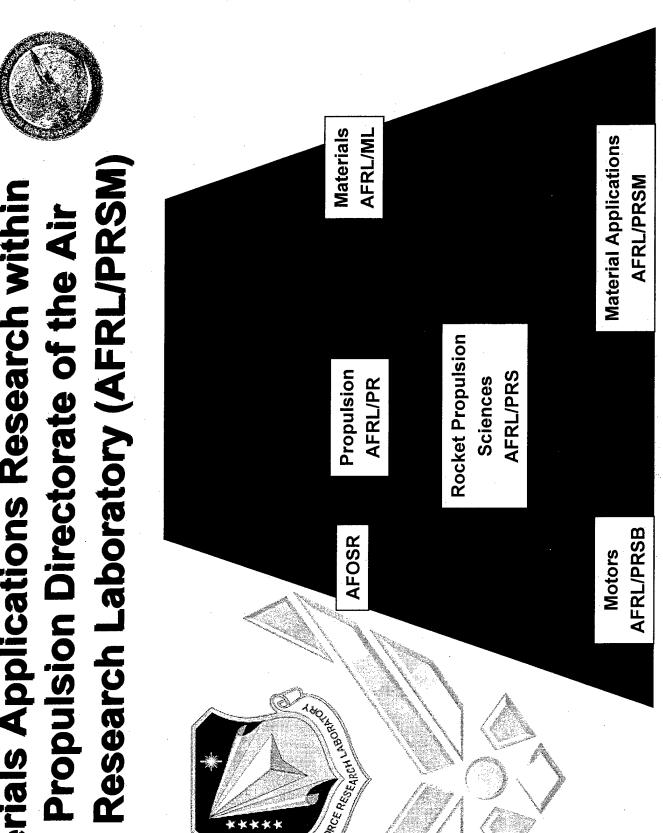
Form Approved REPORT DOCUMENTATION PAGE OMB No. 0704-0188 Public reporting burden for this collection of information is estimated to average 1 hour per response, including the time for reviewing instructions, searching existing data sources, gathering and Public reporting ourden for trils collection of information is estimated to average 1 hour per response, including the time for reviewing instructions, searching existing data sources, gathering and maintaining the data needed, and completing and reviewing this collection of information. Send comments regarding this burden estimate or any other aspect of this collection of information, including suggestions for reducing this burden to Department of Defense, Washington Headquarters Services, Directorate for Information Operations and Reports (0704-0188), 1215-bifferson Davis Highway, Suite 1204, Arlington, VA 22202-4302. Respondents should be aware that notwithstanding any other provision of law, no person shall be subject to any penalty for failing to comply with a collection of information if it does not display a currently valid OMB control number. PLEASE DO NOT RETURN YOUR FORM TO THE ABOVE ADDRESS. 3. DATES COVERED (From - To) 2. REPORT TYPE 1. REPORT DATE (DD-MM-YYYY) Viewgraph Presentation 27-01-03 5a. CONTRACT NUMBER 4. TITLE AND SUBTITLE **5b. GRANT NUMBER** Material Applications Research within the Propulsion Directorate of the Air Force Research Laboratory 5c. PROGRAM ELEMENT NUMBER **5d. PROJECT NUMBER** 6. AUTHOR(S) 4847 5e. TASK NUMBER Dr. Shawn H. Phillips 0249 5f. WORK UNIT NUMBER 8. PERFORMING ORGANIZATION 7. PERFORMING ORGANIZATION NAME(S) AND ADDRESS(ES) REPORT NUMBER Air Force Research Laboratory (AFMC) AFRL-PR-ED-VG-2003-017 AFRL/PRSM 10 E. Saturn Blvd. Edwards AFB, CA 93524-7860 10. SPONSOR/MONITOR'S 9. SPONSORING / MONITORING AGENCY NAME(S) AND ADDRESS(ES) ACRONYM(S) Air Force Research Laboratory (AFMC) 11. SPONSOR/MONITOR'S AFRL/PRS NUMBER(S) 5 Pollux Drive AFRL-PR-ED-VG-2003-017 Edwards AFB CA 93524-7048 12. DISTRIBUTION / AVAILABILITY STATEMENT Approved for public release; distribution unlimited. 13. SUPPLEMENTARY NOTES 14. ABSTRACT

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16. SECURITY CLASSIFICATION OF:		17. LIMITATION OF ABSTRACT	18. NUMBER OF PAGES	19a. NAME OF RESPONSIBLE PERSON Leilani Richardson	
a. REPORT	b. ABSTRACT	c. THIS PAGE	A		19b. TELEPHONE NUMBER (include area code) (661) 275-5015
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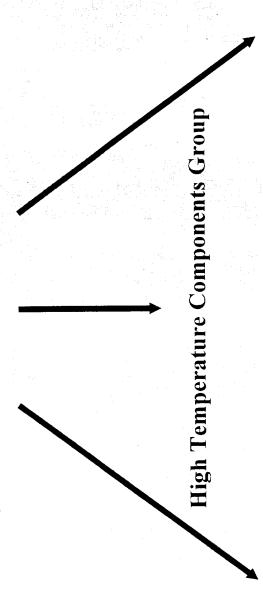
15. SUBJECT TERMS

Force Research Laboratory (AFRL/PRSM) Materials Applications Research within the Propulsion Directorate of the Air



as its Mission to Apply and Transition Materials Technology Research Laboratory, the Material Applications Branch has "Seated within the Propulsion Directorate of the Air Force to Rocket Propulsion."

Dr. Shawn H. Phillips Chief, AFRL/PRSM Air Force Research Lab, Edwards



Polymer Working Group

Fracture Mechanics Group

Air Force Research Laboratory (Edwards) **HWY 395** Integrated High Payoff Rocket Propulsion Technology SCALE IN MILES RESERVATION BOUNDARY BORON MERCURY BLVD, ROCKET SITE ROA ROGERS DRY LAKE (IHPRPT) **HWY 58** 140th STREE WETC. EDWARDS AIR FORCE BA TYNCASTER BLVD ROSAMOND BLVD. **AVENUE E** ROSAMOND DRY LAKE) LANCASTER MOJAVE HIGHWAY 14

Research Focus within AFRL/PRSM

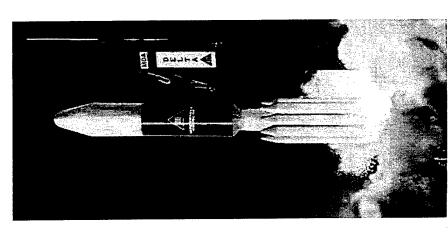


High Temperature Components

- Rapid Densification of Carbon-Carbon
- · Microtube Technology
- Scale-up and Commercialization of Rapid Densification of Carbon-Carbon



- Structure/Property Relationships
- Thermo/Mechanical Improvement of Polymers
- Space-survivable Materials and Coatings
- Scale-up and Commercialization of POSS Nanotechnology



Rapid Densification of Carbon-Carbon

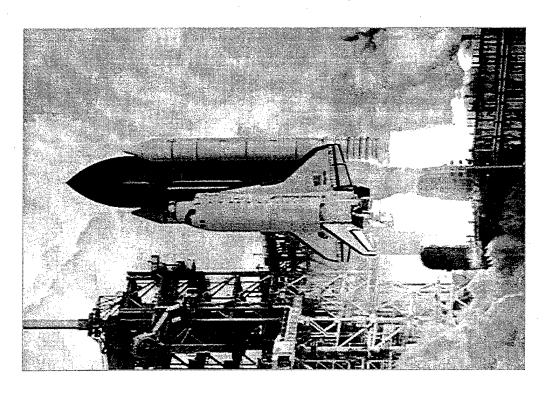


Carbon-Carbon Advantages

- Excellent High Temperature Structural Material
- Very Reliable in Rocket Nozzles,
 Exit Cones, Nosetips, and Leading
 Edges As Well As Aircraft Brakes

Drawbacks to Carbon-Carbon

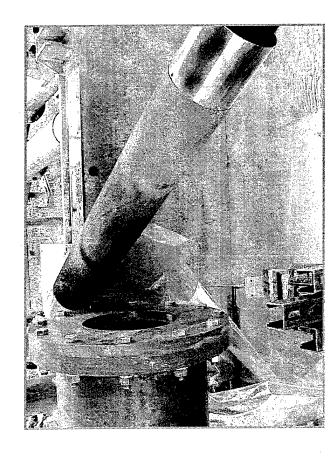
- SOTA Production of Carbon
 Is Very Expensive
- Carbon-Carbon Oxidizes at High
 Temperature in the Presence of
 Oxidizers



Objectives



- composites from many months to less than two weeks. Decrease the processing time of Carbon-Carbon
- Cut the densification cost in half.



Carbon-Carbon part densified in less than two weeks

Rapid Densification of Carbon-Carbon

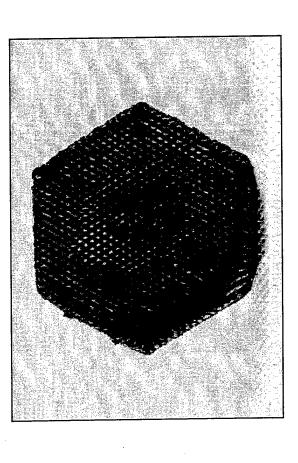


Technical Challenge:

With Conventional Liquid Phase Processes There Is Incomplete Penetration of the Liquids Due To:



- b.) High Surface Tension
- c.) Gassing of Precursor



With Gas Phase Processes There Is Incomplete Penetration of the Gases Due to Their Decomposition on the Outer Surface

Rapid Densification of Carbon-Carbon

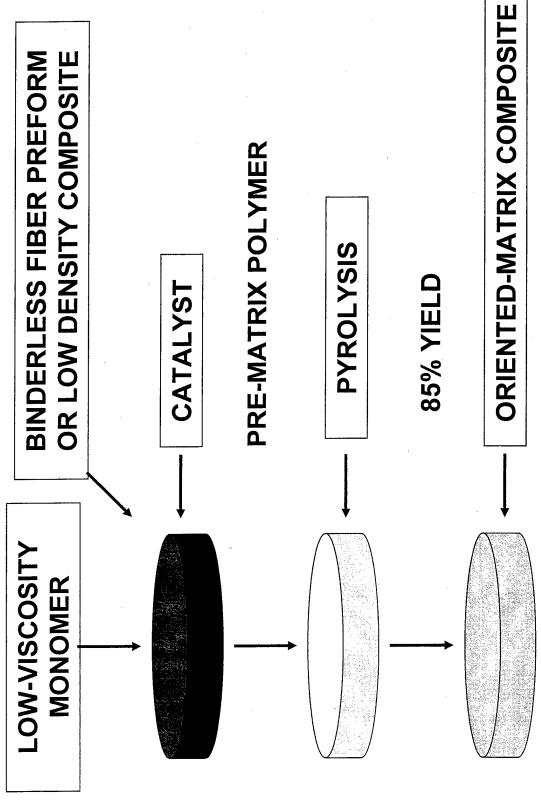


Technical Approach:

- For Liquid Processes Use an Impregnant That
- a.) A High Carbon to Hydrogen Ratio (Char Yield)
- b.) Low Viscosity
- c.) Wets the Fiber Preform.
- In Normal Processing It Is Impossible to Get This Combination of Properties
- High Char Yield Needs High Molecular Weight
- Low Viscosity and Wetting Require Low Molecular Weight

In-Situ Formation of Carbon and Ceramic Matrices

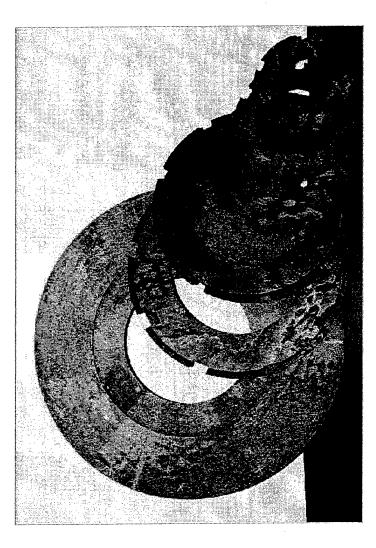




Process Advantages



- Very Uniform Density
- Can Densify Thick Composite
- Complex Geometries
- No Need to Graphitize No Need to Machine Between Densification



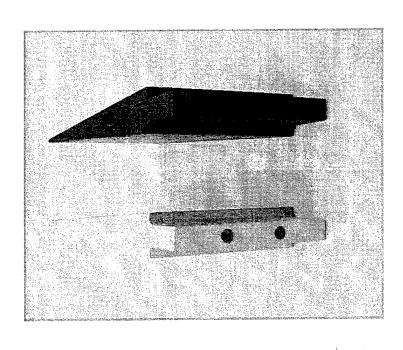
Compatible With Vapor-grown High-conductivity Fibers

Cycles

- Dual Use: Carbon-Carbon Brakes and Electronic Thermal Management

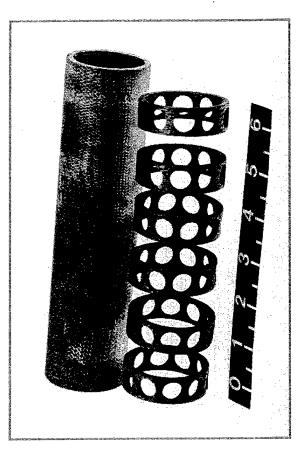
Accomplishments





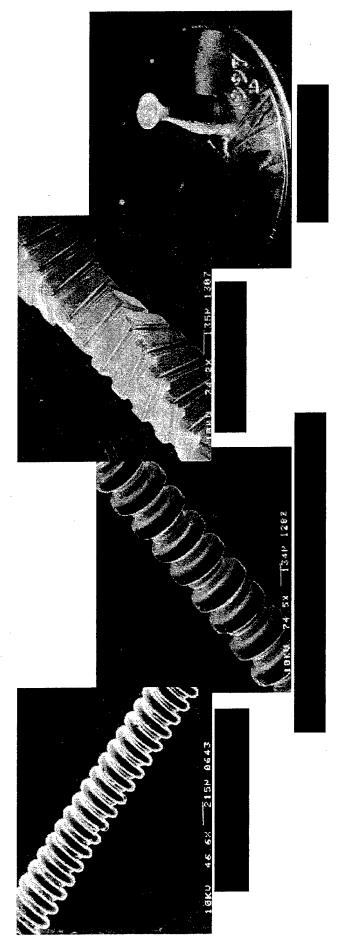
Technology Transfer to SMJ Carbon is ongoing with a cooperative research agreement.

- Large Reactors have been
 Designed....Installed Allowing Scale-up to
 18" Diameter and 60" Length.
- A Large (10" X 10" X 8") Preform and a 5' X 8" Tube Were Uniformly Densified With High Quality Matrix in 2 Weeks. (Not Possible With Other Processes)



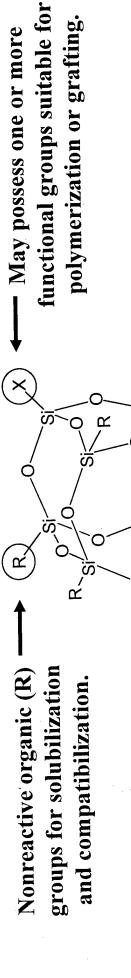
Microdevice Fabrication and Micropropulsion





- Revolutionary method can make any 3-D micron scale shape from any material--1st reliable 3-D manufacturing method
- Heat exchangers, sensors, ducts and valves have all been successfully made using this process

Anatomy of a Polyhedral Oligomeric Silsesquioxane (POSS®) Molecule



ď

Thermally and chemically companically robust hybrid (organic-inorganic) framework.

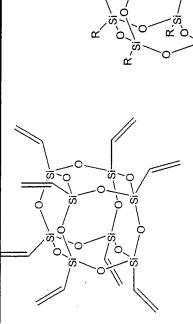
Nanoscopic in size with an Si-Si distance of 0.5 nm and a R-R distance of 1.5 nm.

Precise three-dimensional structure for molecular level reinforcement of polymer segments and coils.

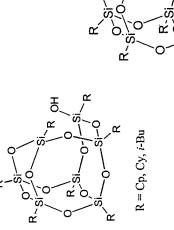
POSS®

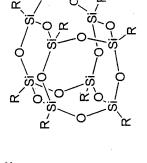
Completely Condensed

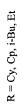
Incompletely Condensed



R = Me, Et, i-Bu, Cp,Cy, i-Octyl, Ph



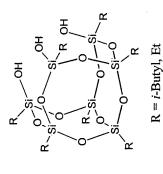








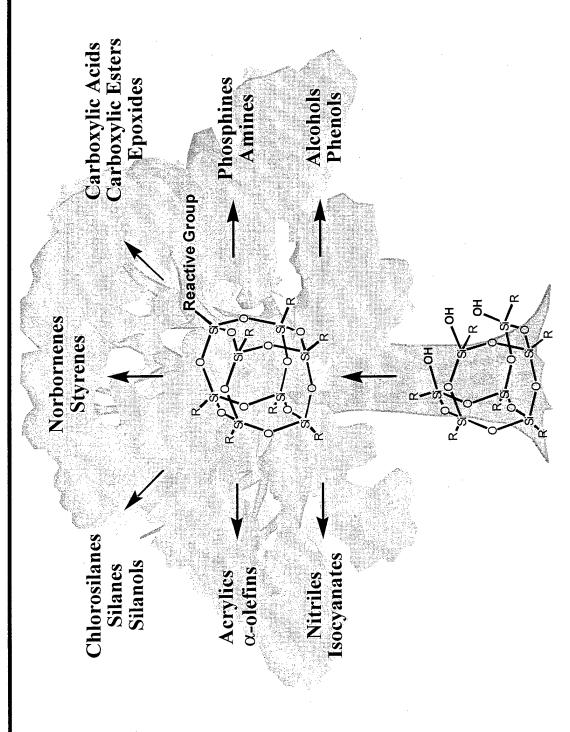




>180 POSS Monomers are commercially available!!

www.hybridplastics.com

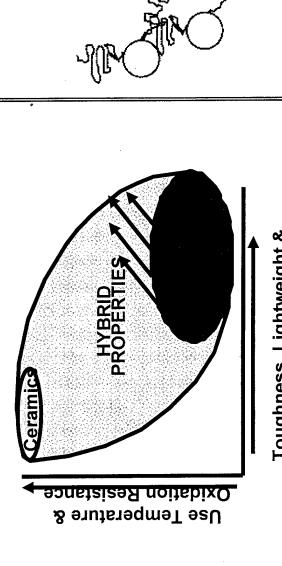
Functionalized POSS®-Monomers



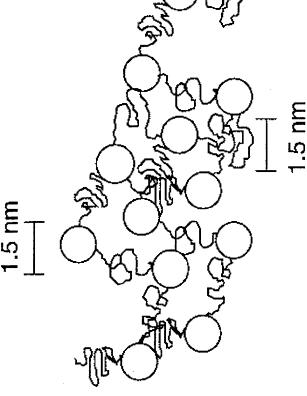
Hybrid Plastics currently offers over 180 NanostructuredTM Chemicals

Key Aspects of POSS® Technology

Hybrid (inorganic/organic) Composition

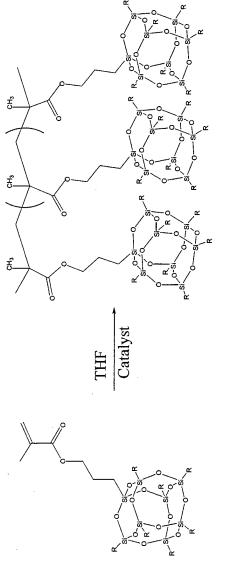


Nanostructured™ Chemical Reinforcement



Toughness, Lightweight & Ease of Processing

POSSTM technology does not require manufacturers to retool or alter existing processes.

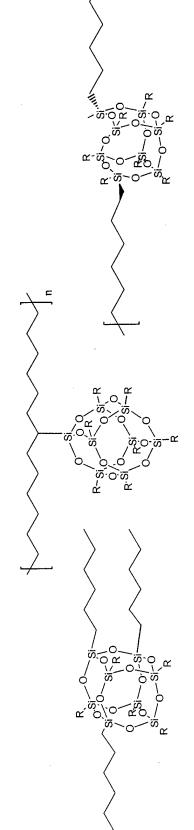


Lichtenhan et. al. Macromolecules 1993, 26, 2141. Lichtenhan, Polym. Mater. Encyclopedia 1996, 10, 7768.



POSS® Polymer Incorporation

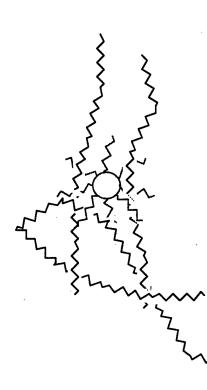




Cross-linker

Pendant Polymer

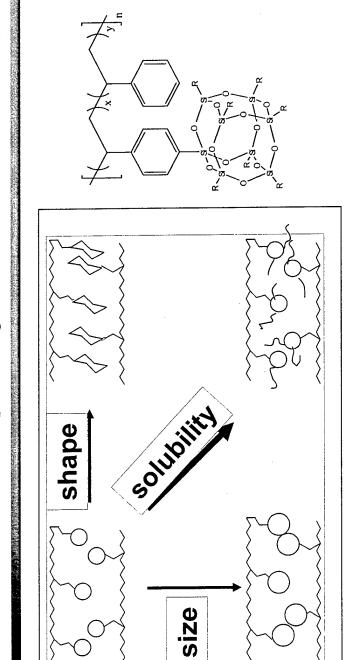
Bead Copolymer



POSS Blending



Structure/Property Relationships





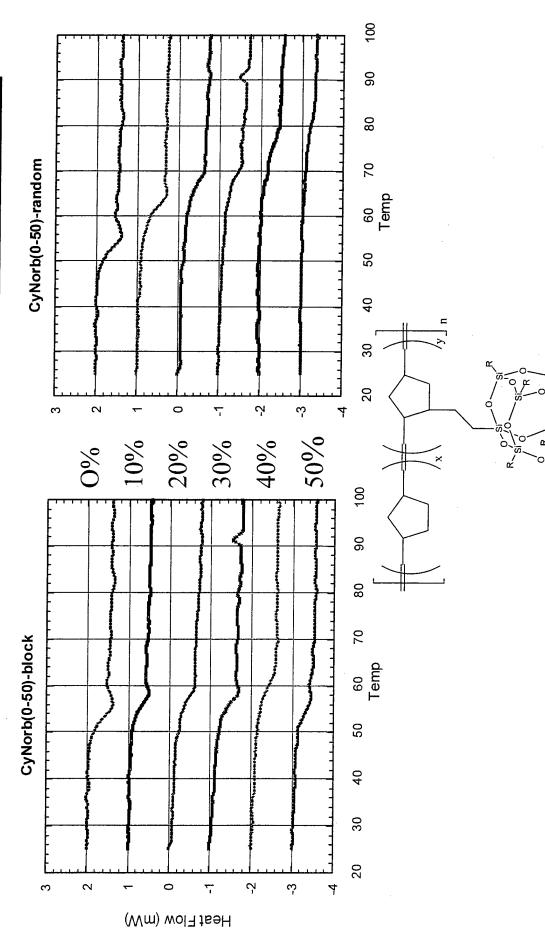






DSC Data for POSS®-Norbornenes



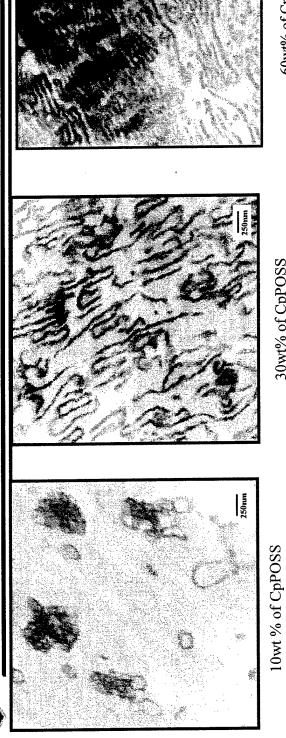


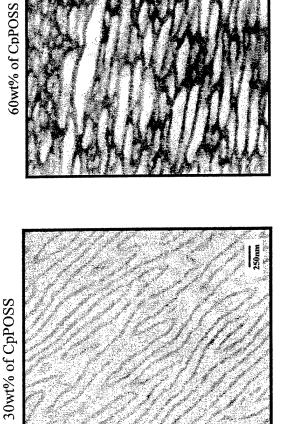
R = Cyclohexyl or Cylcopentyl

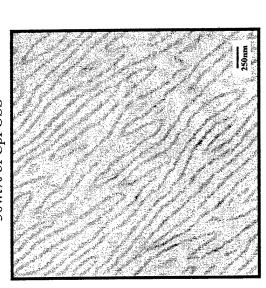
Pat Mather, AFRL

TEM of Diblock POSS®-Norbornenes





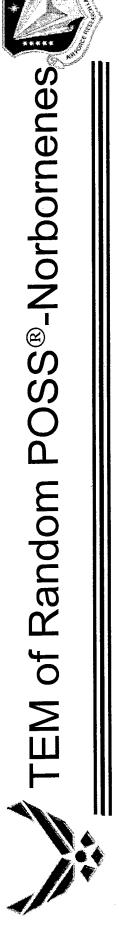




30wt % of CyPOSS

10wt% of CyPOSS

60wt% of CyPOSS

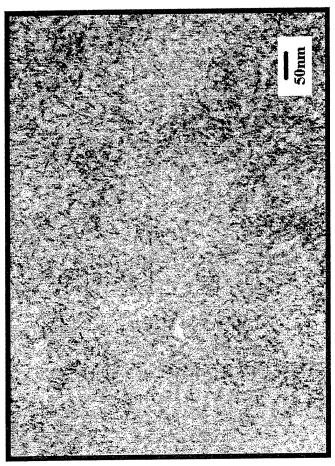


50CyPOSS/PN





'Coarse" Cylinder Nanostructure (Diameter ~ 12nm)



"Fine" Cylinder Nanodstructure (Diameter ~ 6nm)

Since the glass transition improvement is almost double when R=cyclohexyl, then cyclohexyl POSS-rich domains may entrain more unoriented polynorbornene chains than Cyclopentyl POSS-rich domains.

Pat Mather, AFKL

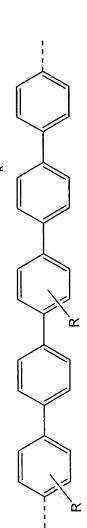


Thermo/Mechanical Improvement of Polymers



POSS®-Kapton® (polyimide)

POSS®-Styrenes



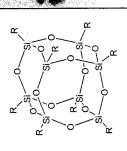
Maxdem's PARMAX™ polymer



compatibility with polymer matrix Importance of R groups: Affect

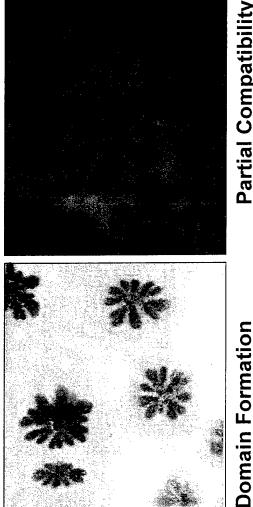


50 Wt % POSS Blends in 2 Million MW PS



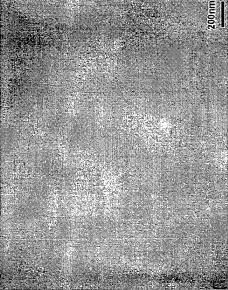
R = cyclopentyl

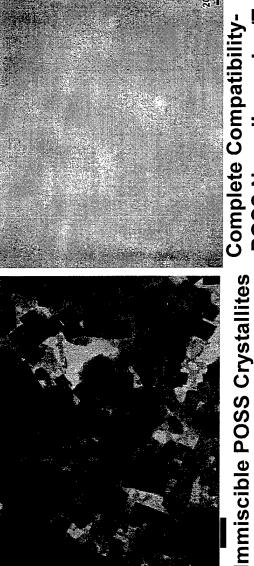




Cp₇T₈Styryl R = cyclopentyl

Partial Compatibility





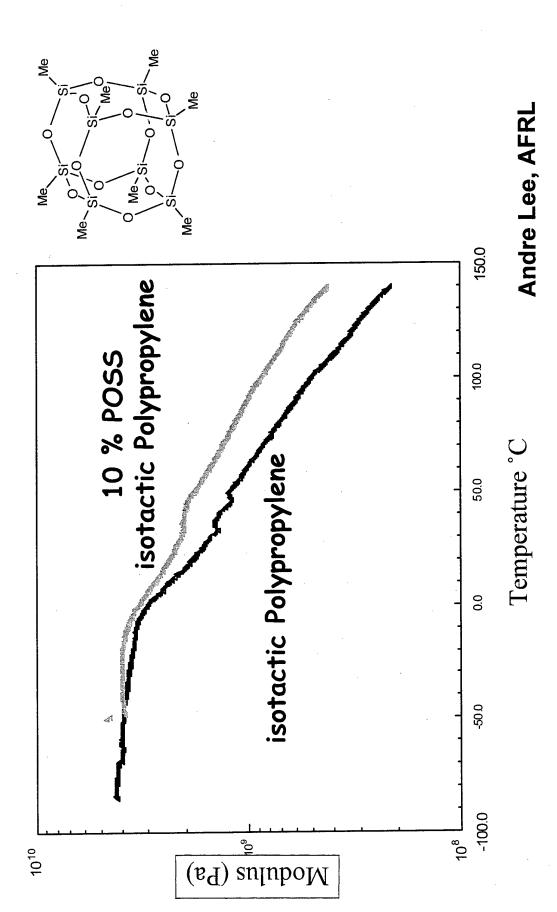
Phenethyl₈T₈ **POSS Nanodispersion/Transparent** Complete Compatibility-

Blanski, et al., Polymer Preprints, 2000, 41(1): p. 585.



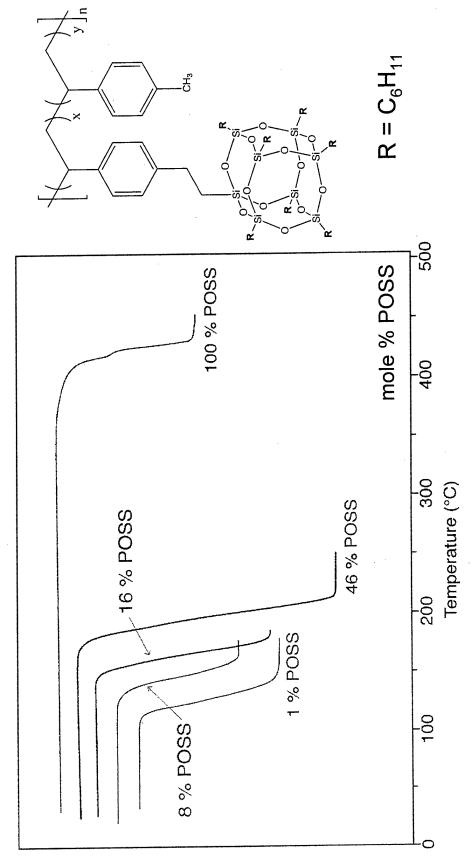
DMA of 10 Wt% POSS® in isotactic **Polypropylene**







TMA Plot For POSS® Styrenes (R = Cyclohexyl)

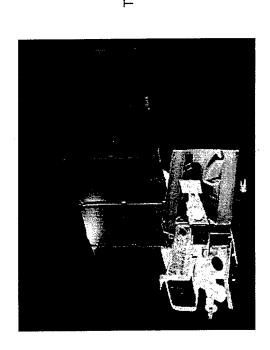


Total TMA Dimension Change - 5 mm

POSS® Materials for Space

Critical for Increasing Lifetime





POSS®-PDMS copolymers

Satellites & Space Systems

POSS Nanocomposite Payoffs

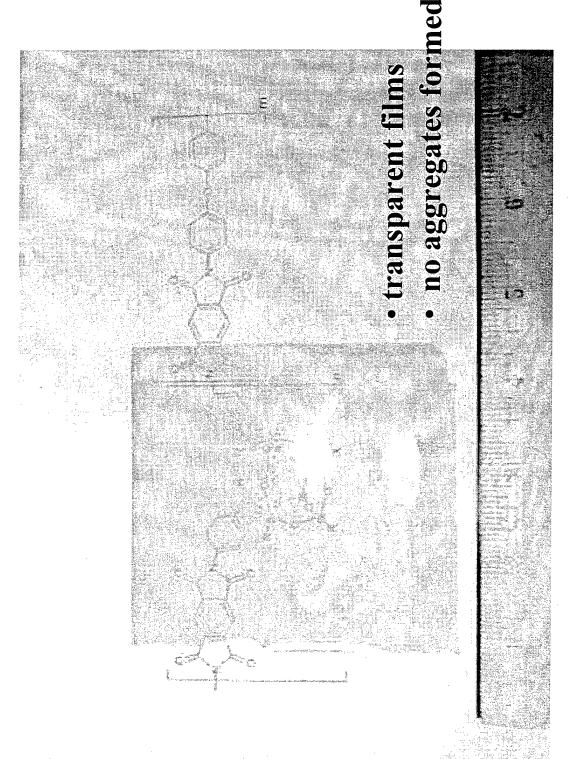
- Maximum Space Survivability
 LEO, AO, VUV, Impact
- Lower Density 'Filler'
- High Modulus
- Resins for all Structural Applications

Simulated 3 mo. AO/VUV Exposure

- 9-20x greater AO resistance than current state of art
- Even better AO/VUV resistance
- Passivation layer demonstrated

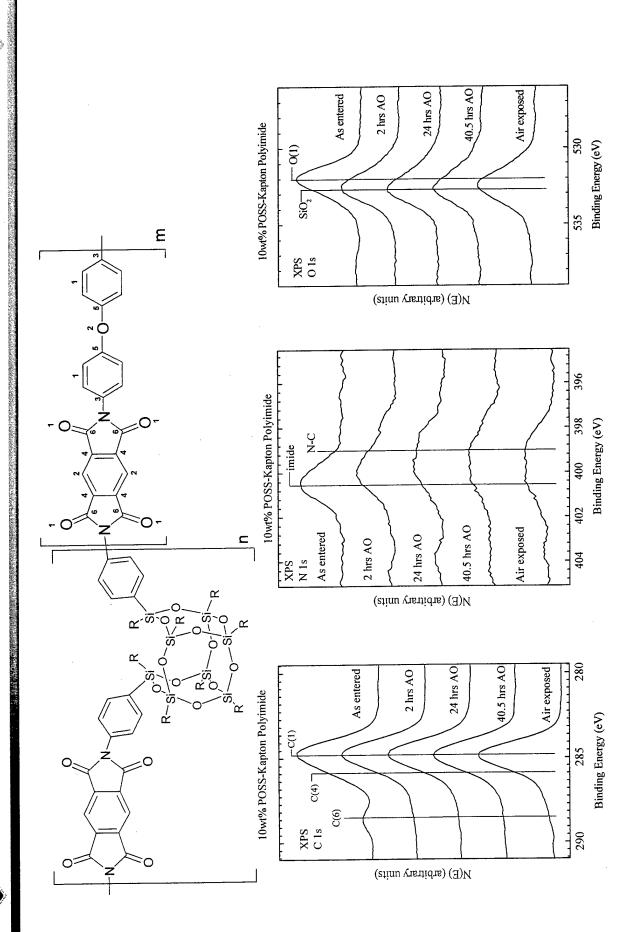










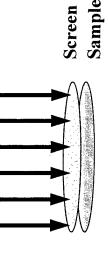




Independent Verification of Oxidation Resistance 🤻



Hyperthermal AO Beam O-Atom Etching Experiment (~10 DAYS IN LEO) Total AO fluence of 8.47 x 1020 atoms cm-2



Kapton 10 wt% POSS®

Kapton H Standard

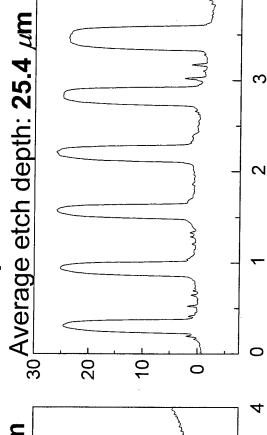
Average etch depth: **2.2** μ**m**

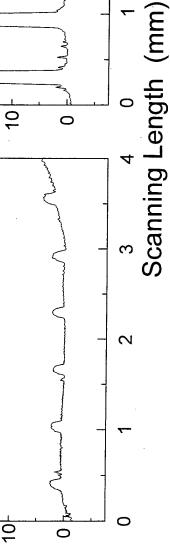
20

Depth

Etch

(m₁)



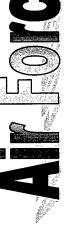


29 Significantly improved oxidation resistance due to a rapidly formed, ceramiclike, passivating and self-healing silica layer preventing further degradation of underlying virgin polymer.

POSS®-Technology Timeline Commercialization:

		1		1
	The POSS Solutions Center		2002	
Low-cost POSS developed	•		2000	
Lov Pr	Ton-level production		1999	_
_	Tor		1998 1999	
Kilo-plant production		_	1995	
Kilc	OSS POSS-platform in systematically developed		991 1993 1994	
	တ		199:	
sts	POSS in polymer	Ces		
POSS in catalysts		dvan	1989 1	
	POSS model for silica	Technical Advances	1985	tones
GE/Brown POSS Trisilanol	Bu	Techr	1965	Milestones
5 ⊢	1st POSS Dow Corning GE		1945	







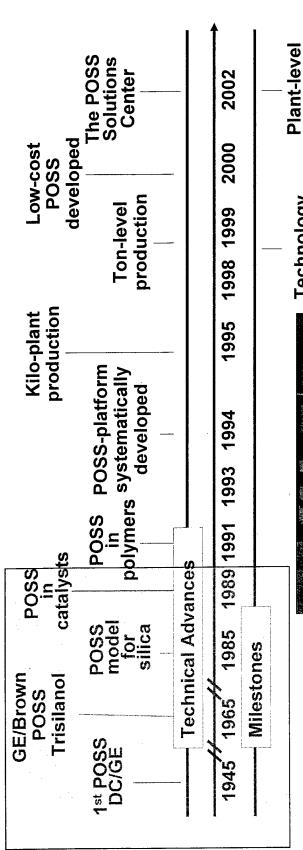
production Plant-level

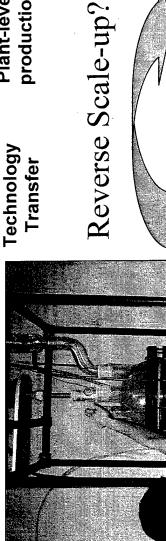
> **Technology Iransfer**



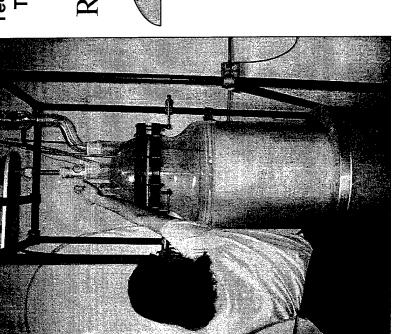
Chemistry

Commercial Solutions

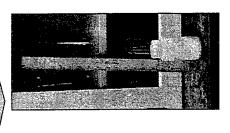


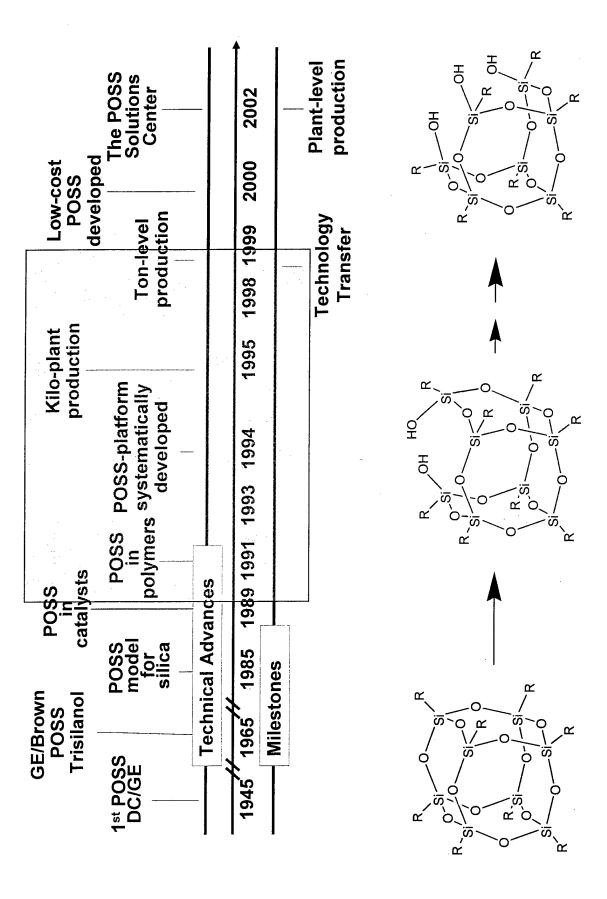


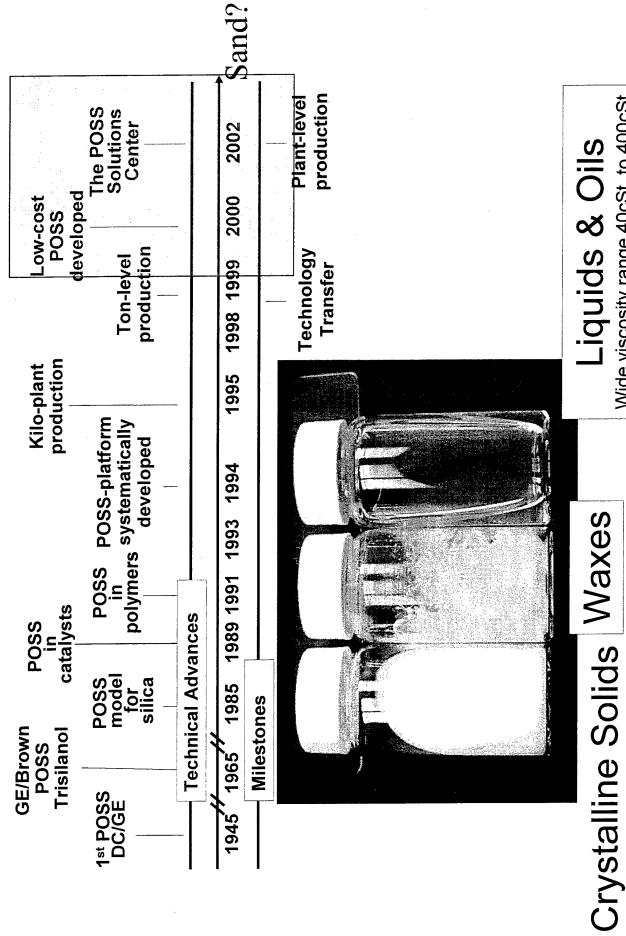
production



R = Cy







-iquids & Oils

Wide viscosity range 40cSt. to 400cSt

Wide melting range 24°C to 400°C+

POSS® Applications

R&D Through Market Development

Monomers & Polymers

Composites

Packaging

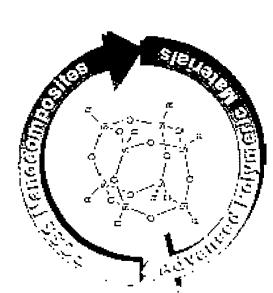
Electronics

Medical

Aerospace

R&D Chemicals and Nanotechnology Markets

Aldrich Chemical Co. Gelest Inc. Hybrid Plastics



Catalysis Metathesis Epoxidation Ligands Supports

Biology & Agriculture

Drug Delivery
Medical Prosthetics
Pharmaceuticals
Antifungal Agents

Blendable Agents Viscosity Modifiers Processing Aids Fire Retardants Performance Additives Corrosion Resistance